

This is a division of Application Serial No. 09/681,820, filed June 11, 2001.

A marked-up version of amended paragraph 23 of the specification is provided in Attachment A, submitted herewith.

Please substitute the following paragraph for Paragraph 23 in the Specification:

a¹
Each ETP generating means shown in FIGURE 1 is fitted with plasma nozzle 16 (although a nozzle is not a required aspect of the invention), whereby plumes 17 of plasma are produced which contact one side of substrate 12. Each plume 17 has a central axis 18 and said central axes are spaced from each other at a distance D. As shown, plumes 17 intersect each other and there is an area of the substrate contacted by both plumes, and this will generally be the case as described in detail hereinafter.

In the Claims:

Please cancel Claims 1-23, without prejudice.

A marked-up version of amended Claim 24 is provided in Attachment A, submitted herewith.

Please substitute the following for pending Claim 24:

a²
24. (Amended) A method for coating a substrate which comprises generating a set of at least two expanding thermal plasma plumes to produce plasma enhanced chemical vapor deposition or PECVD of a coating on said substrate, each of said plumes in said set having a central axis, wherein said central axes of said plasma plumes are oriented parallel to each other.

REMARKS

Applicants have submitted herewith a division of Application Serial No. 09/681,820, filed June 11, 2001, and respectfully request that the accompanying

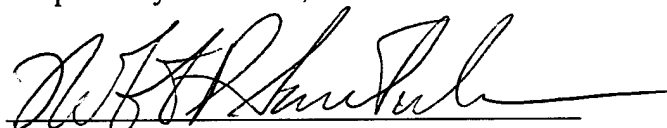
Serial No. 10/063,094

RD-27,190-3

Preliminary Amendment be entered. Claims 1-23 have been canceled, without prejudice.
As such, Claims 24-36 remain in the case.

The Examiner is invited to telephone the Applicants' counsel at the number provided below in order to resolve any outstanding issues concerning the present application.

Respectfully submitted,



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ATTACHMENT AMarked -up version of amended Paragraph 23 of the specification:

Each ETP generating means shown in FIGURE 1 is fitted with plasma nozzle 16 (although a nozzle is not a required aspect of the invention), whereby plumes 17 of plasma are produced which contact one side of substrate 12. Each plume 17 has a central axis 18 and said central axes are spaced from each other [from each other] at a distance D. As shown, plumes 17 intersect each other and there is an area of the substrate contacted by both plumes, and this will generally be the case as described in detail hereinafter.

A marked-up version of amended Claim 24 is provided below.

Marked-up version of Claim 24:

24. (Amended) A method for coating a substrate which comprises generating a set of at least two expanding thermal plasma plumes to produce plasma enhanced chemical vapor deposition or PECVD of a coating on said substrate, each of said plumes in said set having a central axis, wherein said central axes of said plasma plumes are [being codirectionally] oriented parallel to each other.